PATENT ASSIGNMENT

Electronic Version v1.1 Stylesheet Version v1.1

SUBMISSION TYPE:	NEW ASSIGNMENT
NATURE OF CONVEYANCE:	ASSIGNMENT

CONVEYING PARTY DATA

Name	Execution Date
DAINIPPON SCREEN MFG. CO., LTD.	09/30/2006

RECEIVING PARTY DATA

Name:	Sokudo Co., Ltd.
Street Address:	K-I Shijo Building, 88 Kankoboko-cho
Internal Address:	Shijodori-Muromachi-Higashiiru, Shimogyo-ku
City:	Kyoto
State/Country:	JAPAN
Postal Code:	600-8009

PROPERTY NUMBERS Total: 1

Property Type	Number
Patent Number:	5762709

CORRESPONDENCE DATA

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ATTORNEY DOCKET NUMBER: 026531-008500US

NAME OF SUBMITTER: Craig C. Largent

Total Attachments: 2

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PATENT REEL: 018524 FRAME: 0843

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ADDITIONAL ASSIGNMENT OF PATENTS

This ADDITIONAL ASSIGNMENT OF PATENTS (this "Assignment") granted by **Dainippon Screen Mfg. Co., Ltd.**, a Japanese *kabushiki kaisha*, ("Transferor") to Sokudo Co., Ltd., a Japanese *kabushiki kaisha*, ("Company") is made effective as of September 30, 2006.

RECITALS

WHEREAS, Transferor desires to transfer and assign to Company, and Company desires to accept the transfer and assignment of all of Transferor's worldwide right, title, and interest in, to, and under such patents and the patent application as set forth in Appendix A; and

NOW THEREFORE, accordance with Section 4.11(a) and Section 7.3 (c) of the Maser Agreement signed by Transferor and Applied Materials, Inc. on May 15, 2006 and for and in consideration of covenants and agreements set forth below and other good and valuable consideration, the receipt and sufficiency of which are hereby acknowledged:

- 1. Transferor hereby additionally assign, delivers, transfers, and conveys unto Company, all right, benefits, title, and interest in and to the patents and the patent application set forth in Appendix A (collectively, the "Patents"), and all future patents which may be granted there from throughout the world and all divisions, reissues, reexaminations, substitutions, continuations, foreign counterparts and extension of the Patents (collectively "Future Patents"); and Transferor hereby authorizes and requests the United States Patent and Trademark Office and other patent offices throughout the world to issue all Future Patents, insofar as Transferor's interest is concerned, to Company.
- 2. Transferor will execute any and all powers of attorney, applications, assignments, declarations, affidavits, and any other papers in connection therewith reasonably necessary to perfect such right, benefit, title, and interest in Company.

IN WITNESS WHEREOF, Transferor has caused this Assignment to be executed by its duly authorized corporate officer effective as of the date first written above.

Dainippon Screen Mfg. Co., Ltd.

Name: Masahiro Hashimoto

Its: President & COO Date: October 20, 2006

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PATENT REEL: 018524 FRAME: 0844

DNS Ref. No. Title County Application No. Filing Date Publication No. Publication Date Publication Date Beat No. Publication Date Season Seas		Patents ar	nd Paten	t Applications	to transfer f	Patents and Patent Applications to transfer from DNS to Sokudo	opn		
D. Apparatus for Exposing Periphery of an Object KR 90-06042 Filing Date Publication No. Publication Date Apparatus for Exposing Periphery of an Object KR 90-06042 1990/4/28 91-19141 1991/11/30 Apparatus for Exposing Periphery of an Object US 95-2502 1995/12/20 96-21171 1996/17/18 Spin Coating Apparatus US 577827 1996/12/20 96-21171 1996/9/4 Method of and Apparatus for Processing Substrate JP H08-051137 1996/4/17 n/a n/a Method of and Apparatus for Forming Film on Substrate by Sensing Atmospheric Pressure US 662216 1996/4/17 n/a n/a Coating Method of Coating Solution KR 96-286/6/1 996/6/1 n/a n/a Substrate Spin Coating Apparatus US 680983 1996/6/1 996/1/1 n/a Apparatus and Method for Development US 997083 1997/1/2 1997/1/2 Apparatus and Method of Coating Solution US 997083 1997/1/2 1/a Coating Method of Coating Method									
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Apparatus for Exposing Periphery of an Object US 004788 1993/1/14 n/a n/a Spin Coating Apparatus and Method KR 95-52502 1995/12/20 96-21171 1996/7/18 Apparatus For Processing Substrate US 577827 1996/12/22 n/a n/a Method of and Apparatus For Processing Substrate by Coating Method of Coating Solution US 662216 1996/4/17 n/a n/a Coating Method of Coating Solution US 662216 1996/6/11 97-359 1997/1/21 Substrate Spin Coating Apparatus KR 96-28567 1996/7/16 97-339 1997/1/21 Apparatus and Method of Coating Apparatus US 680983 1996/7/16 97-8330 1997/1/21 Apparatus and Method for Development JP H09-110816 1997/4/28 H10-303103 1998/7/1/3 Developing Apparatus and Developing Method US 997/4/28 1998/7/1/2 10/a 1998/7/1/3 Developing Apparatus and Developing Method US 1999/4/3 2002/11/26 2003/18/26 Developing Apparatus, Idemmal proce	P04993-KR	Apparatus for Exposing Periphery of an Object	줐	90-06042	1990/4/28	91-19141	1991/11/30	69876	1994/1/13
Spin Coating Apparatus and Method KR 95-52502 1995/12/20 96-21171 1996/718 Apparatus For Processing Abparatus US 577827 1995/12/22 n/a n/a Apparatus For Processing Substrate JP H08-051137 1996/3/8 H08-243456 1996/9/24 Method of and Apparatus for Forming Film on Substrate by Sensing Atmospheric Pressure US 633484 1996/4/17 n/a n/a Coating Method of Coating Solution KR 96-2216 1996/4/17 n/a n/a Substrate Spin Coating Apparatus KR 96-28567 1996/7/16 97-359 1997/2/24 Apparatus and Method for Development US 997085 1997/1/2/2 n/a n/a Coating Method of Coating Method US 997083 1997/1/2/2 n/a n/a Developing Apparatus and Developing Method US 997083 1999/1/1/9 n/a n/a Developing Apparatus, thermal processing apparatus, thermal processing apparatus. US 10/926718 2005/0058440 2005/0177	P04993-US	Apparatus for Exposing Periphery of an Object	SN	004788	1993/1/14	n/a	n/a	5289263	1994/2/22
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Substrate Spin Coating Apparatus US 680983 1996/7/16 n/a n/a n/a Apparatus and Method for Development JP H09-110816 1997/4/28 H10-303103 1998/11/13 Developing Apparatus and Developing Method US 997083 1997/12/23 n/a n/a Developing Apparatus and Developing Method US 305911 2002/11/26 2003-185560 2003/10/2 Thermal processing apparatus, thermal processing apparatus US 10/926718 2004/8/26 2005/0058440 2005/3/17	P07330-KR	Substrate Spin Coating Apparatus	줐	96-28567	1996/7/15	97-8330	1997/2/24	244171	1999/11/22
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Developing Apparatus and Developing Method US 305911 2002/11/26 2003-185560 2003/10/2 Thermal processing apparatus, thermal processing and substrate processing apparatus US 10/926718 2004/8/26 2005/0058440 2005/3/17	P11176-KR	Coating Method of Coating Solution	줐	1999-49370	1999/11/9			3655042	2002/12/4
Thermal processing apparatus, thermal processing US 10/926718 2004/8/26 2005/0058440 method, and substrate processing apparatus	P12934-US	Developing Apparatus and Developing Method	SN	305911	2002/11/26	2003-185560	2003/10/2	6752544	2004/6/22
method, and substrate processing apparatus		Thermal processing apparatus, thermal processing	011	40,000,740	000010000	07.000.000	1 2 0 0 0		
	P13352-US	method, and substrate processing apparatus	3	01/076/01	2004/0/20	Z005/0058440	71/6/6002		

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